



<b>Session Title:</b>	<b>[TuG1] Frontier Metrology and Modeling I</b>
<b>Session Date:</b>	<b>November 12 (Tue.), 2024</b>
<b>Session Time:</b>	<b>13:00-14:25</b>
<b>Session Room:</b>	<b>Room G (Meeting Room, 5F, Grand Josun Busan)</b>
<b>Session Chair:</b>	<b>Prof. Hyungtak Seo (Ajou Univ., Korea)</b>

**[TuG1-1] [Plenary]**

**13:00-13:45**

**Process Optimization and Control in Dry Etch**

Ye Feng (Intel, USA)

**[TuG1-2]**

**13:45-14:05**

**Etch Rate Uniformity Monitoring for Photoresist Etch Using Multi-Channel Optical Emission Spectroscopy in an Inductively Coupled Plasma Reactor**

Sang Hee Han, Sanghoon Lee, Jaehyeon Kim, Eunchong Park, and Heeyeop Chae (Sungkyunkwan Univ., Korea)

**[TuG1-3]**

**14:05-14:25**

**Measuring Electrical Resistivity of p-Type Si Wafer with Low Dopant Concentration and Its Dependence on Thermal Donor Formation and Surface Treatments**

Seob Shim, Gyuhyeok Choi, Mingyu Park, and Woosung Lee (SK Siltron, Korea)